FIG.1

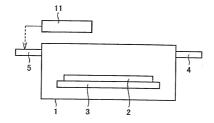
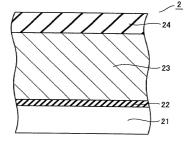


FIG.2



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FIG.3

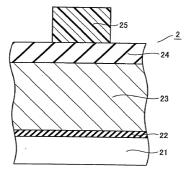


FIG.4

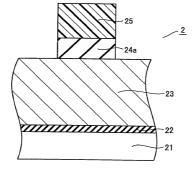


FIG.5

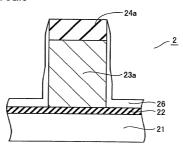
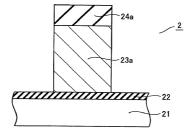
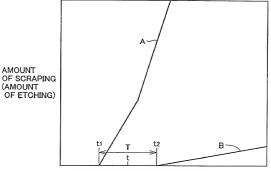


FIG.6





TIME AFTER STARTING SUPPLYING HYDROFLUORIC ACID GAS INTO CHAMBER

FIG.8

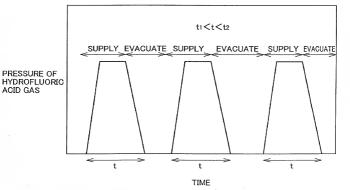


FIG.9

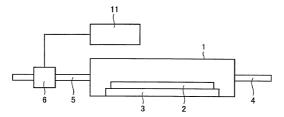


FIG.10

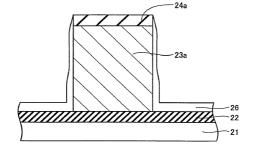


FIG.11

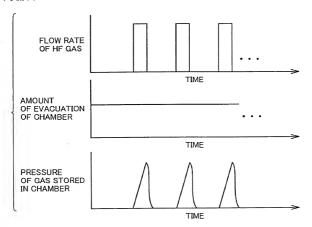


FIG.12

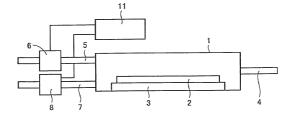


FIG.13

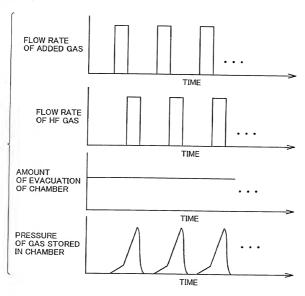


FIG.14

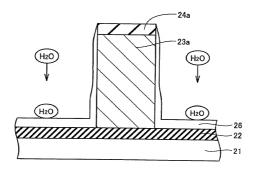


FIG.15

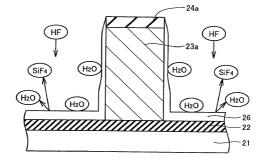


FIG.16

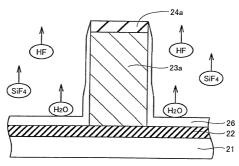
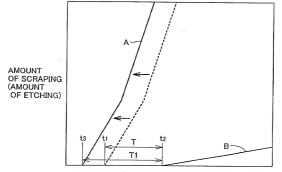


FIG.17



TIME AFTER STARTING SUPPLYING HYDROFLUORIC ACID GAS INTO CHAMBER

FIG.18

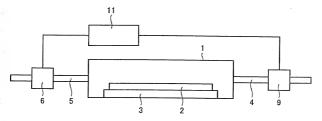


FIG.19

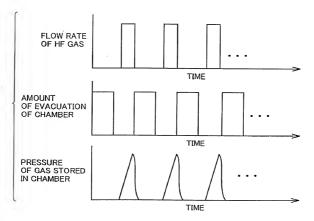


FIG.20

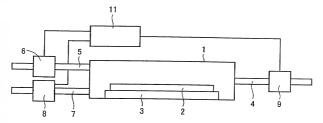


FIG.21

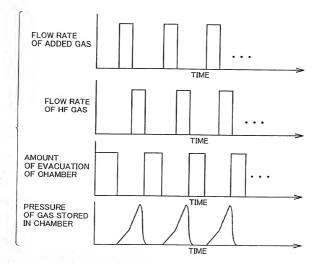


FIG.22

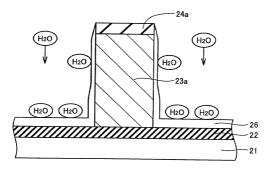
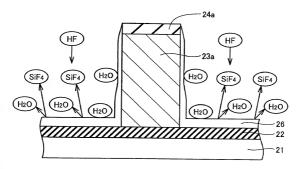


FIG.23



Title: Method of Fabricating Semiconductor Device and Wafer Treatment Apparatus Employed Therefor as well as Semiconductor Device Inventors: SHINTANI ET AL.
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FIG.24

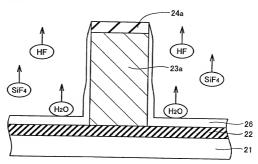


FIG.25

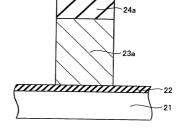


FIG.26

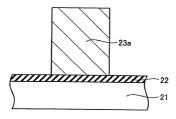


FIG.27 PRIOR ART

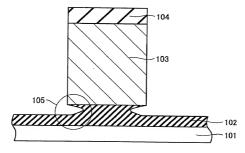
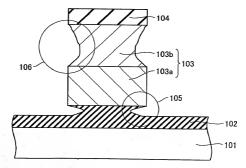


FIG.28 PRIOR ART



Title: Method of Fabricating Semiconductor Device and Wafer Treatment Apparatus Employed Therefor as well as Semiconductor Device Inventors: SHINTANI ET AL. Atty Docket No.: 401352

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FIG.29 PRIOR ART

